



PATENT
Customer No. 22,852
Attorney Docket No. 08137.0004-00000

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Hiroshi SHINRIKI et al.

Serial No.: 09/657,627

Filed: September 8, 2000

For: METHOD OF FORMING A THIN
FILM

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) Group Art Unit: 1762
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) Examiner: B. Chen
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Assistant Commissioner for Patents
Washington, DC 20231

Sir:

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AMENDMENT

In reply to the Notice of Allowance dated January 30, 2002, please amend the application as follows:

IN THE CLAIMS:

Please amend claims 1-5 and 12, as follows:

✓ 1. (Twice amended) A method of forming a thin film on a substrate in a reactor comprising a side having a shower head with a plurality of nozzles and a separate discharge nozzle, the method comprising:

positioning the substrate in the reactor;

heating the substrate to a predetermined temperature;

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